

Chapter 15

\mathcal{H}_2 Control

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\mathcal{H}_2 Norm of Transfer Function

- 1 Transfer matrix

$$G(s) = (A, B, C, D) \quad (1)$$

- 2 \mathcal{H}_2 norm

$$\|G\|_2 := \sqrt{\frac{1}{2\pi} \int_{-\infty}^{\infty} \text{Tr}[G^*(j\omega)G(j\omega)] d\omega} \quad (2)$$

- 3 $g(t)$: inverse Laplace transform of $G(s)$ (namely its impulse response)
- 4 Alternative form (Parseval's theorem)

$$\|G\|_2 = \|g\|_2 = \sqrt{\int_0^{\infty} \text{Tr}[g^T(t)g(t)] dt} \quad (3)$$

Relation with Input and Output

- ➊ SISO: \mathcal{H}_2 norm of a transfer function equals the 2-norm of its impulse response.
- ➋ MIMO: consider an orthonormal set of $\{u_i\}$ ($i = 1, \dots, m$)

$$U^T U = U U^T = I, \quad U = [u_1, \dots, u_m].$$

- ➌ Response to impulse input $w_i(t) = u_i \delta(t)$ is $y_i(t) = g(t)u_i$.
- ➍ Then, \mathcal{H}_2 norm equals the sum of 2-norm of all responses to orthonormal impulse inputs.

$$\begin{aligned} \sum_{i=1}^m \|y_i\|_2^2 &= \sum_{i=1}^m \int_0^\infty y_i^T(t) y_i(t) dt = \sum_{i=1}^m \int_0^\infty u_i^T g^T(t) g(t) u_i dt \\ &= \int_0^\infty \sum_{i=1}^m \text{Tr} \left(g^T(t) g(t) u_i u_i^T \right) dt = \int_0^\infty \text{Tr} \left(g^T(t) g(t) U U^T \right) dt \\ &= \int_0^\infty \text{Tr} \left(g^T(t) g(t) \right) dt = \|G\|_2^2 \end{aligned}$$

Relation with Input and Output

- 1 \mathcal{H}_2 norm equals the variance of steady-state response to a unit white noise
- 2 White noise input $u(t)$:

$$\mathbb{E}[u(t)] = 0 \quad \forall t, \quad \mathbb{E}[u(t)u^T(\tau)] = \delta(t - \tau)I. \quad (4)$$

- 3 Variance of y

$$\begin{aligned} \mathbb{E} \left[y^T(t)y(t) \right] &= \mathbb{E} \left[\int_0^t \int_0^t (g(t-\alpha)u^T(\alpha))g(t-\beta)u(\beta)d\alpha d\beta \right] \\ &= \int_0^t \int_0^t \text{Tr} \left(g^T(t-\alpha)g(t-\beta)\mathbb{E} \left(u(\beta)u^T(\alpha) \right) \right) d\alpha d\beta \\ &= \int_0^t \text{Tr} \left(g^T(t-\beta)g(t-\beta) \right) d\beta = \int_0^t \text{Tr} \left(g^T(\tau)g(\tau) \right) d\tau \\ &\Rightarrow \lim_{t \rightarrow \infty} \mathbb{E} \left[y^T(t)y(t) \right] = \|G\|_2^2. \end{aligned}$$

Weighting Function vs Disturbance/Noise

- 1 Disturbance has dynamics $W(s)$. Then $\hat{y}(s) = G(s)W(s)$.
- 2 Cost function (with weighting function)

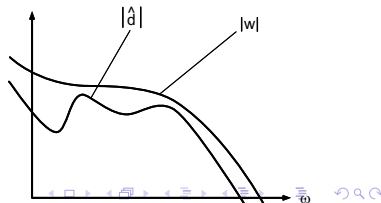
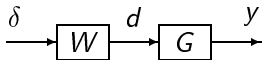
$$\|y\|_2 = \|GW\|_2. \quad (5)$$

- 3 Even when only an upper bound $|W(j\omega)|$ is known,

$$|\hat{d}(j\omega)| \leq |W(j\omega)| \quad \forall \omega, \text{ i.e.}$$

disturbance is still suppressed if $\|GW\|_2$ is minimized because

$$\|G\hat{d}\|_2 \leq \|GW\|_2.$$



Condition for $\|G\|_2 < \gamma$

Lemma 1

The following statements are equivalent.

- ① A is stable and $\|C(sI - A)^{-1}B\|_2 < \gamma$.
- ② There is a matrix $X = X^T > 0$ satisfying

$$XA + A^T X + C^T C < 0, \quad \text{Tr}(B^T X B) < \gamma^2. \quad (6)$$

- ③ There exist matrices $X = X^T$ and $W = W^T$ satisfying

$$\begin{bmatrix} XA + A^T X & C^T \\ C & -I \end{bmatrix} < 0 \quad (7)$$

$$\begin{bmatrix} W & B^T X \\ XB & X \end{bmatrix} > 0, \quad \text{Tr}(W) < \gamma^2. \quad (8)$$

Example: 2-DOF system

- 1 \mathcal{H}_2 norm is ideally suited for rating transient response.
- 2 Input penalty: in reference tracking, the input is a persistent signal in the steady state. We should limit its rate of change instead.
- 3 To remove the steady-state value, we use W_r^{-1} to filter the input.
- 4 For step signal $r(t) = 1(t)$, the input filtered by $W_r^{-1}(s) = s$ becomes its derivative $\dot{u}(t)$.

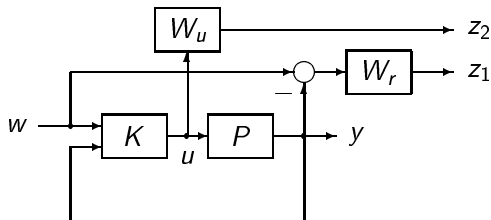


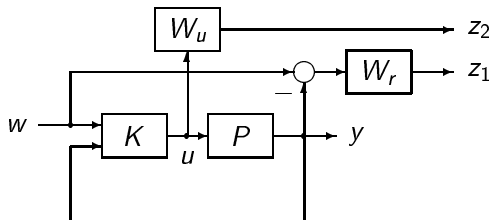
Figure: \mathcal{H}_2 tracking control problem of 2-DOF system

Example: 2-DOF system

1 Generalized plant

$$\begin{bmatrix} z_1 \\ z_2 \\ w \\ y \end{bmatrix} = \begin{bmatrix} W_r & -W_r P \\ 0 & -W_u \\ -I & 0 \\ 0 & P \end{bmatrix} \begin{bmatrix} w \\ u \end{bmatrix} = G \begin{bmatrix} w \\ u \end{bmatrix}$$

2 Minimizing the \mathcal{H}_2 norm of CLS from w to $\begin{bmatrix} z_1 \\ z_2 \end{bmatrix}$, called an \mathcal{H}_2 control problem.



\mathcal{H}_2 control problem

- 1 For any given $\gamma > 0$, design a controller satisfying $\|H_{zw}\|_2 < \gamma$.

$$G(s) = \left[\begin{array}{c|cc} A & B_1 & B_2 \\ \hline C_1 & 0 & D_{12} \\ C_2 & D_{21} & 0 \end{array} \right]. \quad (9)$$

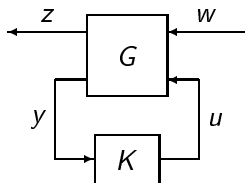


Figure: Generalized feedback system

Solution

Theorem 1

(A, B_2) is stabilizable and (C_2, A) is detectable. Then,

- ① \mathcal{H}_2 control is solvable iff $\exists X = X^T, Y = Y^T, \mathbb{A}, \mathbb{B}, \mathbb{C}, W$ satisfying

$$\text{He} \begin{bmatrix} AX + B_2\mathbb{C} & A & 0 \\ \mathbb{A} & YA + \mathbb{B}C_2 & 0 \\ C_1X + D_{12}\mathbb{C} & C_1 & -\frac{1}{2}I \end{bmatrix} < 0 \quad (10)$$

$$\begin{bmatrix} W & B_1^T & B_1^TY \\ B_1 & X & I \\ YB_1 & I & Y \end{bmatrix} > 0, \quad \text{Tr}(W) < \gamma^2. \quad (11)$$

- ② \mathcal{H}_2 controller is given by

$$A_K = N^{-1}(\mathbb{A} - NB_KC_2X - YB_2C_KM^T - YAX)(M^{-1})^T \quad (12)$$

$$C_K = \mathbb{C}(M^{-1})^T, \quad B_K = N^{-1}\mathbb{B}.$$

(Proof) CLS

$$\left[\begin{array}{c|c} A_c & B_c \\ \hline C_c & D_c \end{array} \right] = \left[\begin{array}{cc|c} A & B_2 C_K & B_1 \\ B_K C_2 & A_K & B_K D_{21} \\ \hline C_1 & D_{12} C_K & 0 \end{array} \right].$$

According to Lemma 1, the \mathcal{H}_2 control problem has a solution iff $\exists P = P^T$ and $W = W^T$ satisfying

$$\begin{bmatrix} PA_c + A_c^T P & C_c^T \\ C_c & -I \end{bmatrix} < 0, \quad \begin{bmatrix} W & B_c^T P \\ PB_c & P \end{bmatrix} > 0, \quad \text{Tr}(W) < \gamma^2.$$

Factorize matrix P as

$$P\Pi_1 = \Pi_2, \quad \Pi_1 = \begin{bmatrix} X & I \\ M^T & 0 \end{bmatrix}, \quad \Pi_2 = \begin{bmatrix} I & Y \\ 0 & N^T \end{bmatrix}.$$

Congruent transformations lead to equivalent inequalities

$$\begin{bmatrix} \Pi_2^T A_c \Pi_1 + (\Pi_2^T A_c \Pi_1)^T & (C_c \Pi_1)^T \\ C_c \Pi_1 & -I \end{bmatrix} < 0, \quad \begin{bmatrix} W & (\Pi_2^T B_c)^T \\ \Pi_2^T B_c & \Pi_2^T \Pi_1 \end{bmatrix} > 0.$$

After concrete computation,

$$\Pi_2^T A_c \Pi_1 = \begin{bmatrix} AX + BC & A + BDC \\ A & YA + BC \end{bmatrix}, \quad \Pi_2^T B_c = \begin{bmatrix} B_1 \\ YB_1 + BD_{21} \end{bmatrix}$$

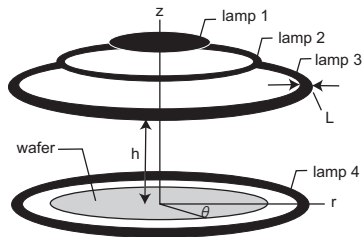
$$C_c \Pi_1 = [C_1 X + D_{12}C \quad C_1], \quad \Pi_2^T \Pi_1 = \begin{bmatrix} X & I \\ I & Y \end{bmatrix}$$

and the conclusion is obtained. ∇

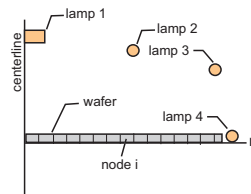
Case Study: \mathcal{H}_2 control of a RTP system

- 1 RTP (rapid thermal processing) system is used for the temperature treatment of semiconductor wafers.
- 2 Besides control design, locations of actuator and sensor are also vital in achieving high performance.
- 3 Three circular lamp zones on top of the wafer and one circumvallating the wafer.
- 4 Lamps 1-3 are for the thermal processing of wafer surface while Lamp 4 is used to compensate for the heat leaking from the side of wafer.
- 5 Pyrometers are installed below the bottom of wafer to measure the temperature.

Lamp location



(a) 3D illustration



(b) Cross section

Figure: RTP system

Model of RTP

- 1 Heat conduction equation of wafer

$$\frac{\partial}{\partial r} \left(kr \frac{\partial T}{\partial r} \right) + \frac{\partial}{\partial \theta} \left(k \frac{\partial T}{\partial \theta} \right) + \frac{\partial}{\partial z} \left(k \frac{\partial T}{\partial z} \right) = \rho C \frac{\partial T}{\partial t}. \quad (13)$$

- 2 Finite element model:

divide the wafer as 20 concentric annular zones with equal areas.

$$m_i C_i \frac{dT_i}{dt} = q_i^{\text{ab}} + q_i^{\text{em}} + q_i^{\text{conv}} + q_i^{\text{cond}}, \quad i = 1, \dots, n \quad (14)$$

Model of RTP

- 1 Emission heat q_i^{em}

$$q_i^{\text{em}} = -\varepsilon_i \sigma A_i T_i^4, \quad \varepsilon_i = \frac{0.7128}{1 + \exp\left(\frac{T_i - 666.15}{-64.70}\right)} \quad (15)$$

- 2 Convection heat q_i^{conv}

$$q_i^{\text{conv}} = -h_i A_i (T_i - T_{\text{gas}}), \quad h_i = 14.2 + 8.6 \left(\frac{r_i}{R} \right) \quad (16)$$

- 3 Conduction heat q_i^{cond}

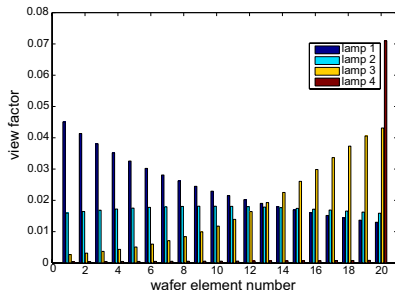
$$q_i^{\text{cond}} = -2\pi k_i Z \left(\frac{T_i - T_{i-1}}{r_i^{\text{cen}} - r_{i-1}^{\text{cen}}} r_i^{\text{in}} + \frac{T_i - T_{i+1}}{r_i^{\text{cen}} - r_{i+1}^{\text{cen}}} r_i^{\text{out}} \right) \quad (17)$$

- 4 Radiation heat q_i^{ab} of lamp

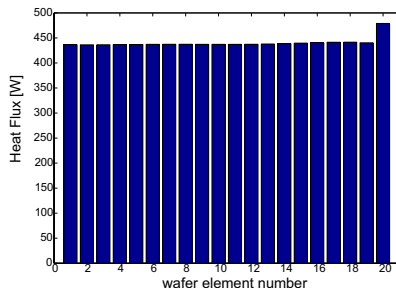
$$q_i^{\text{ab}} = \alpha_i \sum_{j=1}^J L_{ij} P_j. \quad (18)$$

Optimal configuration of lamps

- 1 To realize a high uniformity in the surface temperature, the heat irradiated from the lamps to the wafer surface must be uniform.
- 2 Configuration of lamps needs to be optimized.



(a) View factors between annular zones and lamps



(b) Radiation heat on wafer surface

Location of sensors

- 1 What is important is not only the location of actuator, but also that of the sensor.
- 2 Only finite points are measured. So, it is important to determine the number of sensors and locate them suitably. In correspondence with the number lamp zones, 4 pyrometers are used.
- 3 Sensors are located at the annular zones numbered 3, 11, 18 and 20 where the peaks of temperature fluctuation occur.

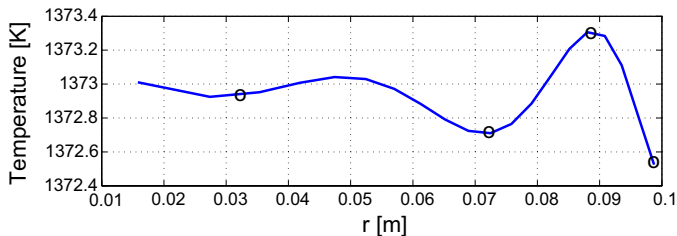


Figure: Steady-state temperature distribution of wafer surface

Specification

- 1 In the whole thermal processing, the maximal temperature fluctuation must be less than ± 1 K.

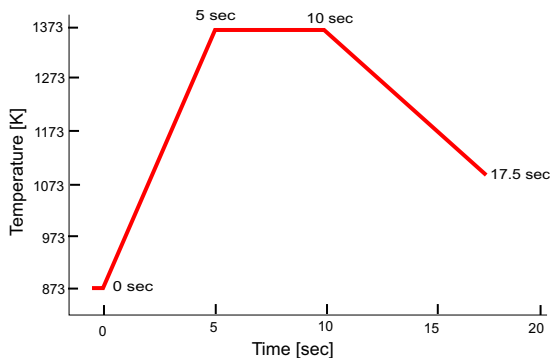


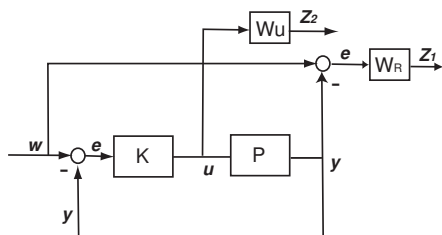
Figure: Reference trajectory of the thermal processing

\mathcal{H}_2 control design

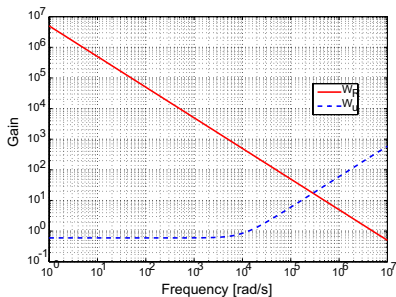
- 1 $T = [T_1, \dots, T_{20}]^T$: temperature, $u = [u_1, \dots, u_4]^T$: lamp power
- 2 Linear approximation about the target temperature 1373 K

$$\Delta \dot{T} = A\Delta T + B\Delta u, \quad y = C\Delta T \quad (19)$$

- 3 $\Delta T = T - T_0$, $\Delta u = u - u_0$: error w.r.t. the equilibrium (T_0, u_0)

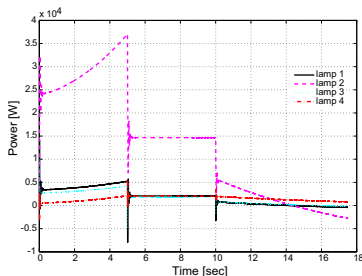


(a) Generalized plant

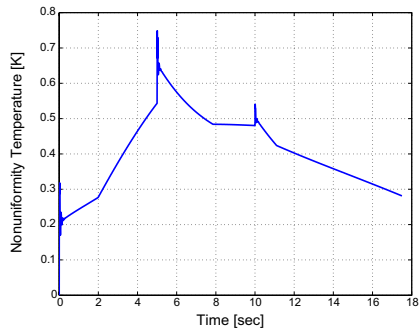


(b) Weighting functions W_R , W_u

Simulation Results: effect of sensor location



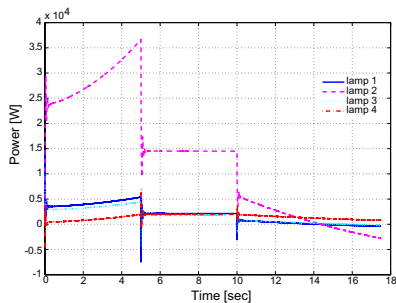
(a) Lamp powers



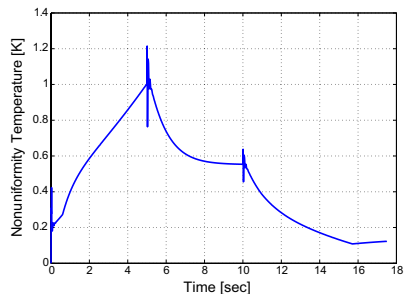
(b) Nonuniformity of temperature

Figure: Result of optimal sensor location

Simulation Results: effect of sensor location



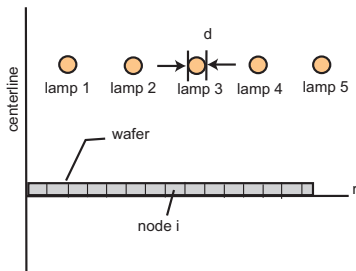
(a) Lamp powers



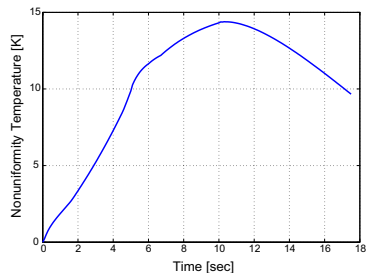
(b) Nonuniformity of temperature

Figure: Result of equal distance sensor location

Simulation Results: effect of lamp location



(a) Lamp configuration



(b) Nonuniformity of temperature

Figure: RTP with lamps located at the same height and equal distance